

21. (Added) The method of claim 20, wherein the plurality of abrasive particles has a hardness comparable to the hardness of the low dielectric constant surface.
22. (Added) The method of claim 20, wherein the plurality of abrasive particles has a surface charge opposite to that of the low dielectric constant surface.
23. (Added) The method of claim 21, wherein the plurality of abrasive particles has a surface charge opposite to that of the low dielectric constant surface.
24. (Added) The method of claim 20, wherein the core material comprises polystyrene-acrylonitrile, Nylon-6, polyoxymethylene, polyurethane and poly(para-divinylphenylene) or mixtures thereof.
25. (Added) The method of claim 20, wherein the coating material is softer than the core material.
26. (Added) A method of planarizing a low dielectric constant surface, comprising:
performing a conventional chemical mechanical planarization; and
buffing with an abrasive slurry wherein the abrasive slurry comprises a plurality of core particles, wherein each core particle comprises a surface and at least one core particle at least one core material; and a coating material that coats the surface of the plurality of core particles, wherein the core particles and the coating material form a plurality of abrasive particles and wherein the density of the coating material is less than the density of the core material.
27. (Added) The method of claim 26, wherein the plurality of abrasive particles has a hardness comparable to the hardness of the low dielectric constant surface.
28. (Added) The method of claim 26, wherein the plurality of abrasive particles has a surface charge opposite to that of the low dielectric constant surface.
29. (Added) The method of claim 27, wherein the plurality of abrasive particles has a surface charge opposite to that of the low dielectric constant surface.